

## WEST Search History

DATE: Monday, November 12, 2007

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<i>DB=PGPB; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L9	US-20050205108-A1.did.	1
<input type="checkbox"/>	L8	US-20050205108-A1.did.	1
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L7	L6 with l4 with l3	4
<input type="checkbox"/>	L6	fluid adj10 surfactant	8159
<input type="checkbox"/>	L5	wafer or semiconductor	2074109
<input type="checkbox"/>	L4	lens or (optical lens)	858425
<input type="checkbox"/>	L3	cleaning or rinsing	999155
<input type="checkbox"/>	L2	L1 or (ILS)	2065754
<input type="checkbox"/>	L1	immersion lithography system	270

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### Search Results - Record(s) 1 through 4 of 4 returned.

1. Document ID: US 20070004182 A1

L7: Entry 1 of 4

File: PGPB

Jan 4, 2007

PGPUB-DOCUMENT-NUMBER: 20070004182

PGPUB-FILING-TYPE:

DOCUMENT-IDENTIFIER: US 20070004182 A1

TITLE: Methods and system for inhibiting immersion lithography defect formation

PUBLICATION-DATE: January 4, 2007

INVENTOR-INFORMATION:

NAME	CITY	STATE	COUNTRY
Chang; Ching-Yu	Yilang City		TW
Lin; Burn Jeng	Hsin-Chu		TW

US-CL-CURRENT: 438/478; 438/947

ABSTRACT:

An immersion lithography system includes an immersion fluid holder for containing an immersion fluid. The system further includes a stage for positioning a resist-coated semiconductor wafer in the immersion fluid holder and a lens proximate to the immersion fluid holder and positionable for projecting an image through the immersion fluid and onto the resist-coated semiconductor wafer. The immersion fluid holder includes a coating configured to reduce contaminant adhesion from contaminates in the immersion fluid.

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2. Document ID: US 20050205108 A1

L7: Entry 2 of 4

File: PGPB

Sep 22, 2005

PGPUB-DOCUMENT-NUMBER: 20050205108

PGPUB-FILING-TYPE: new

DOCUMENT-IDENTIFIER: US 20050205108 A1

TITLE: Method and system for immersion lithography lens cleaning

PUBLICATION-DATE: September 22, 2005

## INVENTOR-INFORMATION:

NAME	CITY	STATE	COUNTRY
Chang, Ching-Yu	Yen-Sun		TW
Lin, Chin-Hsiang	Hsin-Chu		TW

US-CL-CURRENT: 134/1; 355/53

## ABSTRACT:

A method and system for cleaning lens used in an immersion lithography system is disclosed. After positioning a wafer in the immersion lithography system, a light exposing operation is performed on the wafer using an objective lens immersed in a first fluid containing surfactant, wherein the surfactant reduces a likelihood for having floating defects adhere to the wafer and the objective lens.

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 3. Document ID: US 4613380 A

L7: Entry 3 of 4

File: USPT

Sep 23, 1986

US-PAT-NO: 4613380

DOCUMENT-IDENTIFIER: US 4613380 A

TITLE: Method for removing lipid deposits from contact lenses

DATE-ISSUED: September 23, 1986

## INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Chen; Jie	Midland	MI		

US-CL-CURRENT: 134/30; 134/26, 134/42

## ABSTRACT:

This invention relates to a method for removing lipid deposits from contact lenses of a polymeric material, particularly contact lenses wherein at least a portion of the polymeric material is an organosilicon compound, by contacting the contact lens surfaces with certain volatile methylsiloxane fluids such as octamethylcyclotetrasiloxane and thereafter removing the fluid and the lipids removed from the contact lens. This method is especially useful for removing lipid deposits from silicone elastomer contact lenses.

24 Claims, 0 Drawing figures

Exemplary Claim Number: 17

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4. Document ID: US 20050205108 A1

L7: Entry 4 of 4

File: DWPI

Sep 22, 2005

DERWENT-ACC-NO: 2005-682085

DERWENT-WEEK: 200570

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TITLE: Lens cleaning method for e.g. very large-scale integrated circuit, involves performing light exposing operation on wafer with lens immersed in fluid, and cleaning lens with another fluid having surfactant-spiked fluid

INVENTOR: CHANG, C; LIN, C

PRIORITY-DATA: 2004US-0802087 (March 16, 2004)

## PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
<u>US 20050205108 A1</u>	September 22, 2005		011	B08B003/12

INT-CL (IPC): A61N 5/00; B08B 3/12; B08B 6/00; B08B 7/00; B08B 7/02; G03B 27/42; G21G 5/00

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